Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	27	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and conformable with mask and etch\$3. clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR ·	ON	2007/03/28 13:52
L2	0	"6475369".pn. And clean\$3 with anode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:53
L3	1	"6475369".pn. And etch\$3 with anode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:58
L4	1	"6475369".pn. And pulse	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:59
L5	1	"6475369".pn. And puls\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 14:08
L6		"734223".ap.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 14:09
S1	54	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and conformable with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 13:34
S2	13	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and conformable with mask and clean\$3 with (mask electrode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:39

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S3		("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and conformable with mask and clean\$3 with (electrode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR.	ON	2007/03/27 13:55
S4	2209	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and clean\$3 with (electrode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 14:24
S 5	99	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (clean\$3 with (electrode)) with (etching anodizing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 14:34
S6	19	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (clean\$3 with (electrode)) with (anodizing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 14:41
S7	19	("205"/\$.ccls. "204"/\$.ccls.) and (clean\$3 with (electrode)) with (anodizing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 14:41
S8		("205"/\$.ccls. "204"/\$.ccls.) and (clean\$3 with (electrode)) with (anodizing) not S6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 14:42
S9	445	("205"/\$.ccls. "204"/\$.ccls.) and (electrode) with (anodizing) not S6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 14:42
S10	31	("205"/\$.ccls. "204"/\$.ccls.) and (electrode) with (anodizing) and clean\$3 with (electrode) not S6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 14:42

S11	9	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and conformable with mask and pulse\$2 with (current voltage)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:07
S12	9	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and conformable with mask and frequency	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:09
S13	6585	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and frequency	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:09
S14	58	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and frequency and periodic with reverse	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:17
S15	1720	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and frequency with (hz khz)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:18
S16	370	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and frequency with (hz khz) and pulse with current	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:21
S17	161	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) same frequency with (hz khz) and pulse with current	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:36
S18		("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and conformable with mask and sequestering	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:43

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S19	20	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and sequestering same edta	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:46
S21	0	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and conformable with mask and edta	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR ,	ON	2007/03/27 15:43
S22	276	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and complexing same edta	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:46
S23	41	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and complexing same edta same advantag\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:51
S24	16	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and complexing same edta same solubility	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 16:02
S25	89	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and wetting and accelerator and suppressor and leveler	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 16:04
S26	206	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (carrier wetting) and (brightener accelerator) and suppressor and leveler	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 16:05

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